

<b>Notice of References Cited</b>	Application/Control No. 10/617,919		Applicant(s)/Patent Under Reexamination PATEL ET AL.	
	Examiner Hugh Jones		Art Unit 2128	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,810,296	10-2004	Bode et al.	700/110
*	B	US-6,928,628	08-2005	Seligson et al.	716/4
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Friedberg; First principle-based state estimator for photolithography control using full profile metrology; MS thesis; pp. 1-78; 5/2003.
	V	Panoramic Technology; five pages of printout from website (for 9/2002) describing Panoramic v3.01.
	W	Pistor; A new photoresist simulator from panoramic Technology; printout from website (for 9/2002) describing Panoramic v3.01; pp. 1-10; 10/2002.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.